

Product Comparison

IST RPX-210

Competition - Silane Deposition

Equipment Size:	Bench Top / R&D and Production	Table Top / R&D Labs
Chamber Dimension:	12"x10"x10"	~ 8"x10"x8"
	200mm Wafer Cassette	150mm Wafer Cassette
Chamber Material / Construction:	Structural T6061 Aluminum (Machined from a Solid Block) 100% Corrosion Proof	Welded 316 Stainless Steel
Temperature Uniformity:	$\pm 1^{\circ}\text{C}$	$\pm 3^{\circ}\text{C}$
Chamber Temperature:	RT to 130°C	~ near 200°C
Clean Room Compatibility:	Class-10	Class-10
Chemical Dispense:	Vaporization or Carrier Gas Assist metered by Mass Flow	Syringe Pump
Chemical Control Capability:	Partial Pressure control by capacitance manometer	Liquid Dispense Volume onto a Hot Plate
Number of Precursors:	2 precursors in Interchangeable Cartridges + up to 2 gas sources	Up to 3 precursors
Plasma Capable:	Yes	No
	Std: 75KHz @ 100Watts Optional: 13.56Mhz @ 200W	
Software / Control:	Windows-11 OS + LabVIEW® Graphic Interface. Flexible Recipes. Internet enabled. Remote monitoring and control available from anywhere in the world.	A PLC with manual timers.
# of Process Recipes:	Only limited by disk space	up to 6
Power Requirements:	208V - 230VAC	208V - 230VAC